

Title (en)

LIFT SYSTEM COMPRISING A PULLEY, WHOSE CONTACT SURFACE COMPRISSES AN ANISOTROPIC STRUCTURE.

Title (de)

AUFZUGSANLAGE AUFWEISEND EINE ROLLE, DEREN KONTAKTOBERFLÄCHE EINE ANISOTROPE STRUKTUR AUFWEIST.

Title (fr)

INSTALLATION D'ASCENSEUR COMPRENANT UNE POULIE, DONT LA SURFACE DE CONTACT COMPREND UNE STRUCTURE ANISOTROPIQUE.

Publication

**EP 3310701 B1 20190807 (DE)**

Application

**EP 16728290 A 20160607**

Priority

- EP 15172611 A 20150617
- EP 2016062890 W 20160607

Abstract (en)

[origin: WO2016202643A1] In an elevator system, a belt-type suspension means is guided over at least one pulley. A contact surface of the pulley has an anisotropic structure for interacting with the belt-type suspension means. A friction co-efficient between the suspension means and the contact surface in the circumferential direction of the pulley is greater than a friction co-efficient between the suspension means and the contact surface in the axial direction of the pulley.

IPC 8 full level

**B66B 15/04** (2006.01)

CPC (source: CN EP US)

**B66B 11/06** (2013.01 - CN); **B66B 15/02** (2013.01 - US); **B66B 15/04** (2013.01 - CN EP US)

Citation (opposition)

Opponent : OTIS Elevator Company

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Designated contracting state (EPC)

AL AT BE BG CH CY CZ DE DK EE ES FI FR GB GR HR HU IE IS IT LI LT LU LV MC MK MT NL NO PL PT RO RS SE SI SK SM TR

DOCDB simple family (publication)

**WO 2016202643 A1 20161222**; BR 112017022333 A2 20180710; CA 2982511 A1 20161222; CN 107709218 A 20180216;  
CN 107709218 B 20200327; EP 3310701 A1 20180425; EP 3310701 B1 20190807; ES 2748779 T3 20200317; HK 1246757 A1 20180914;  
MX 2017015025 A 20180413; SG 11201709942Y A 20171228; TW 201708092 A 20170301; US 2018162699 A1 20180614

DOCDB simple family (application)

**EP 2016062890 W 20160607**; BR 112017022333 A 20160607; CA 2982511 A 20160607; CN 201680031778 A 20160607;  
EP 16728290 A 20160607; ES 16728290 T 20160607; HK 18106278 A 20180515; MX 2017015025 A 20160607; SG 11201709942Y A 20160607;  
TW 105118371 A 20160613; US 201615736602 A 20160607